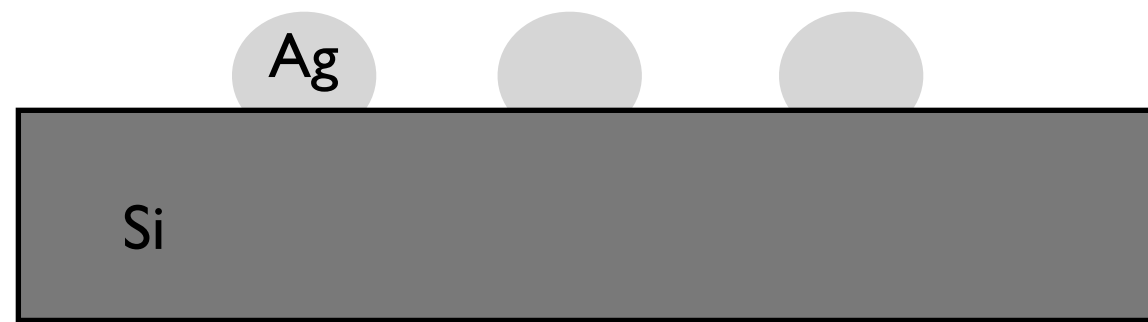
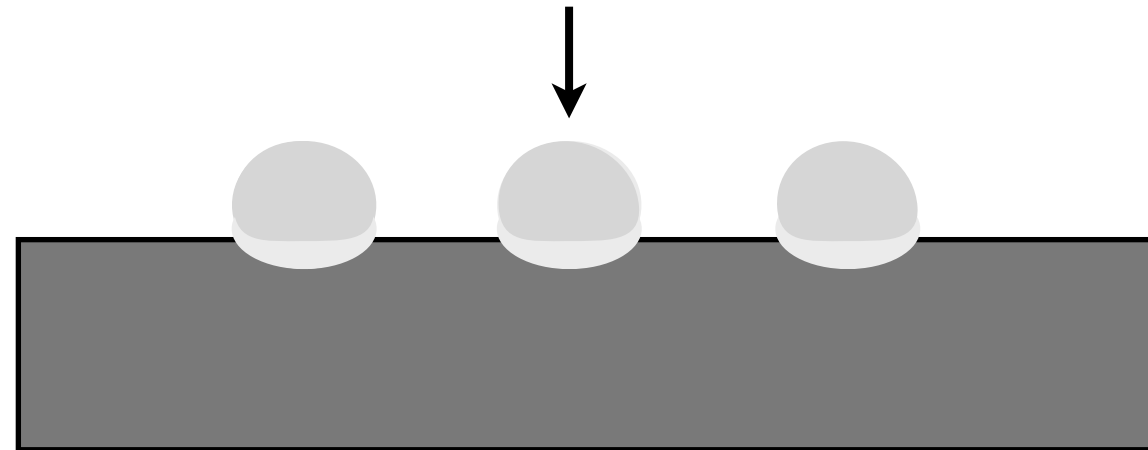


**~200nm a-Si porous
membrane**

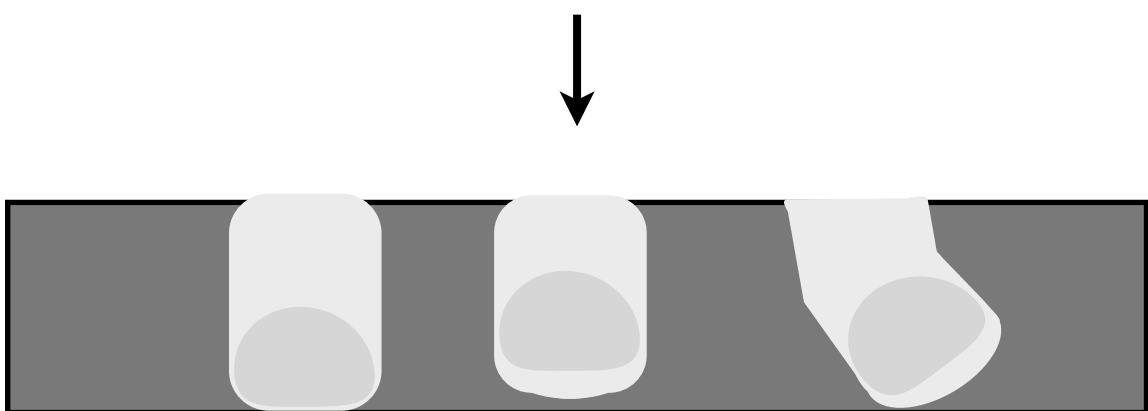
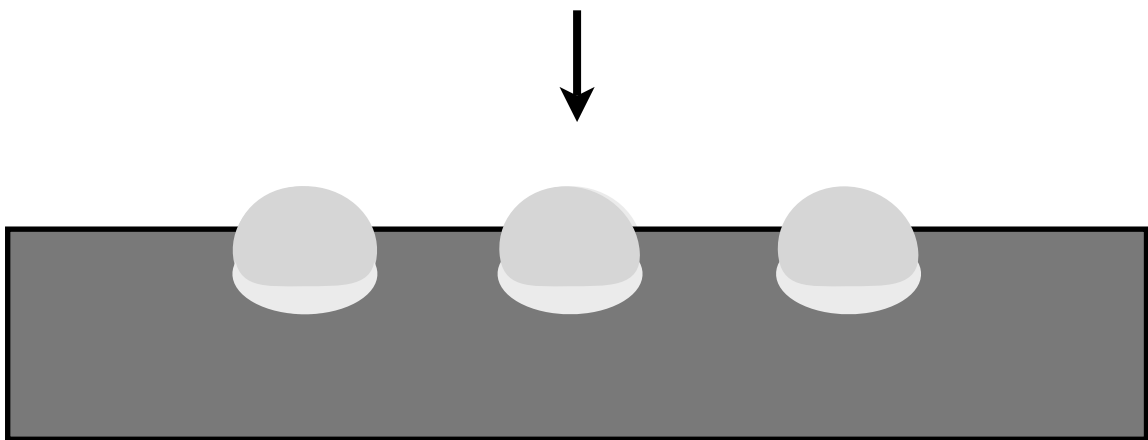
3-2-11



Ag is thermally evaporated on a-Si or c-Si and annealed to form “round” particles.



In a solution of HF and H_2O_2 , the Ag catalyzes the oxidation of Si and HF quickly reacts with the oxide.

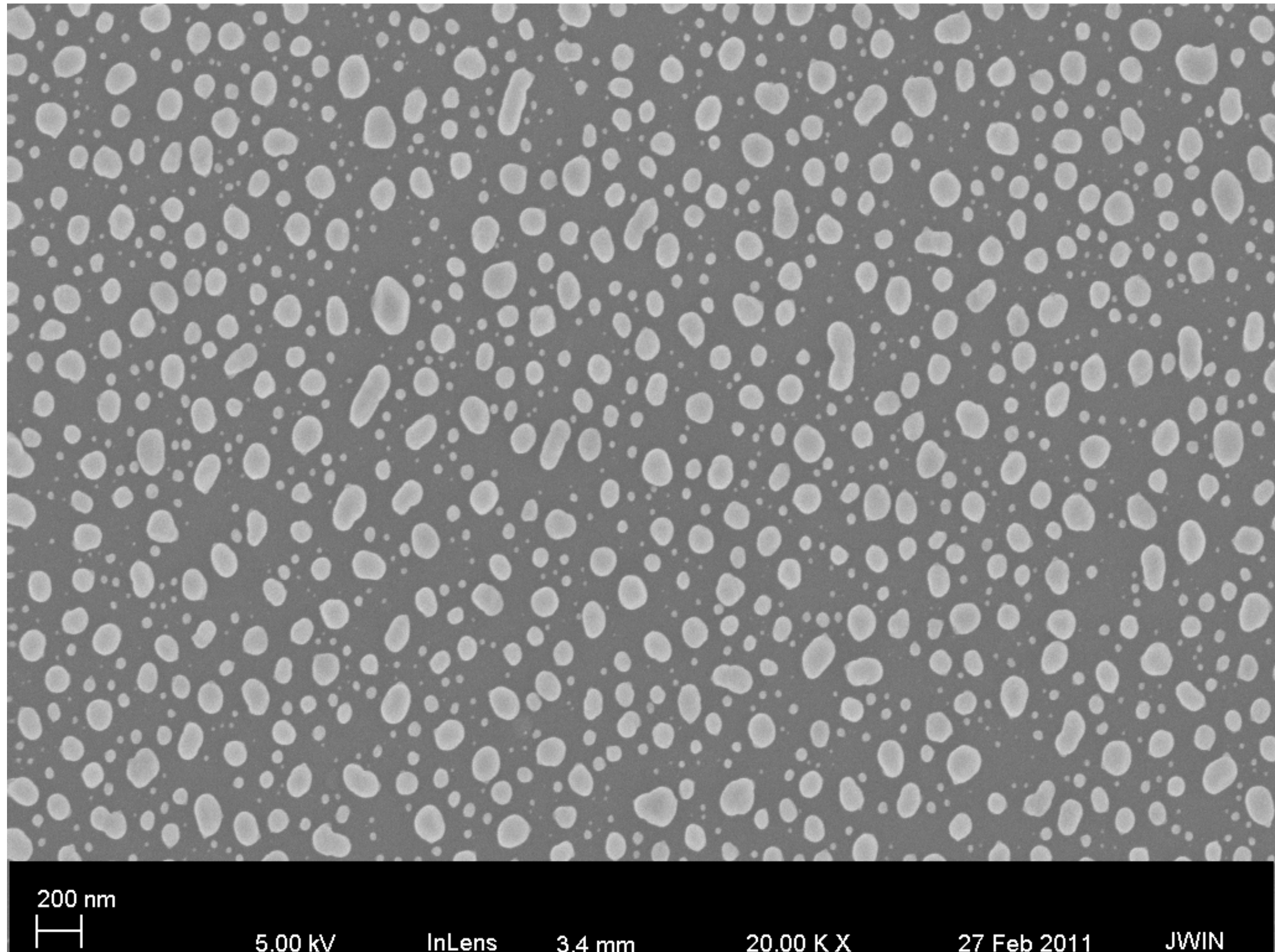


The Ag nanoparticles rapidly “burrow” through the silicon.

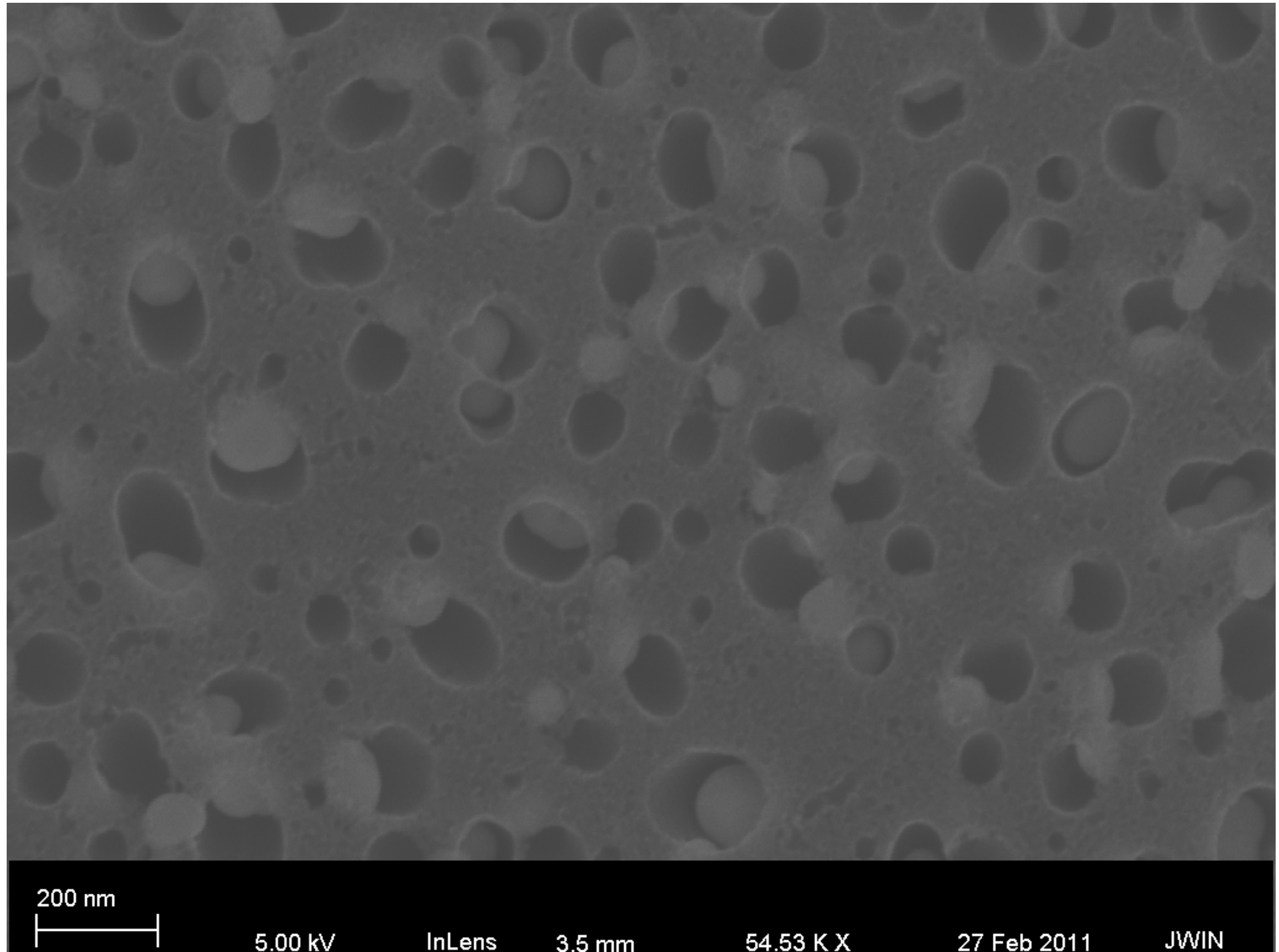
Tsujino and Matsumura. Boring deep cylindrical nanoholes in silicon using silver nanoparticles as a catalyst. Adv Mater (2005) vol. 17 (8) pp. 1045-+

Tsujino and Matsumura. Helical nanoholes bored in silicon by wet chemical etching using platinum nanoparticles as catalyst. Electrochem Solid St (2005) vol. 8 (12) pp. C193-C195

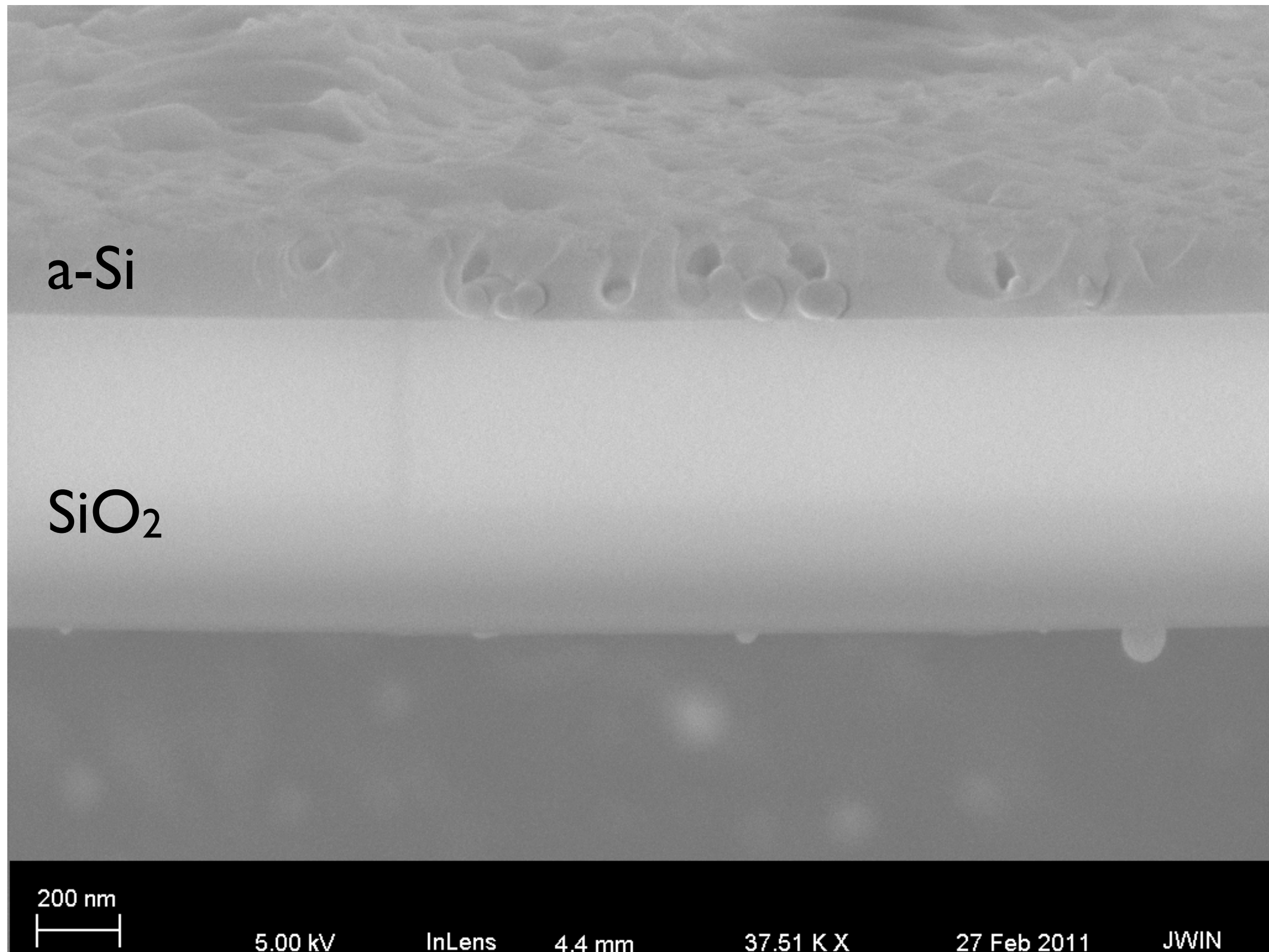
Thermally evaporated Ag after 300 °C anneal in Ar for 1 hr

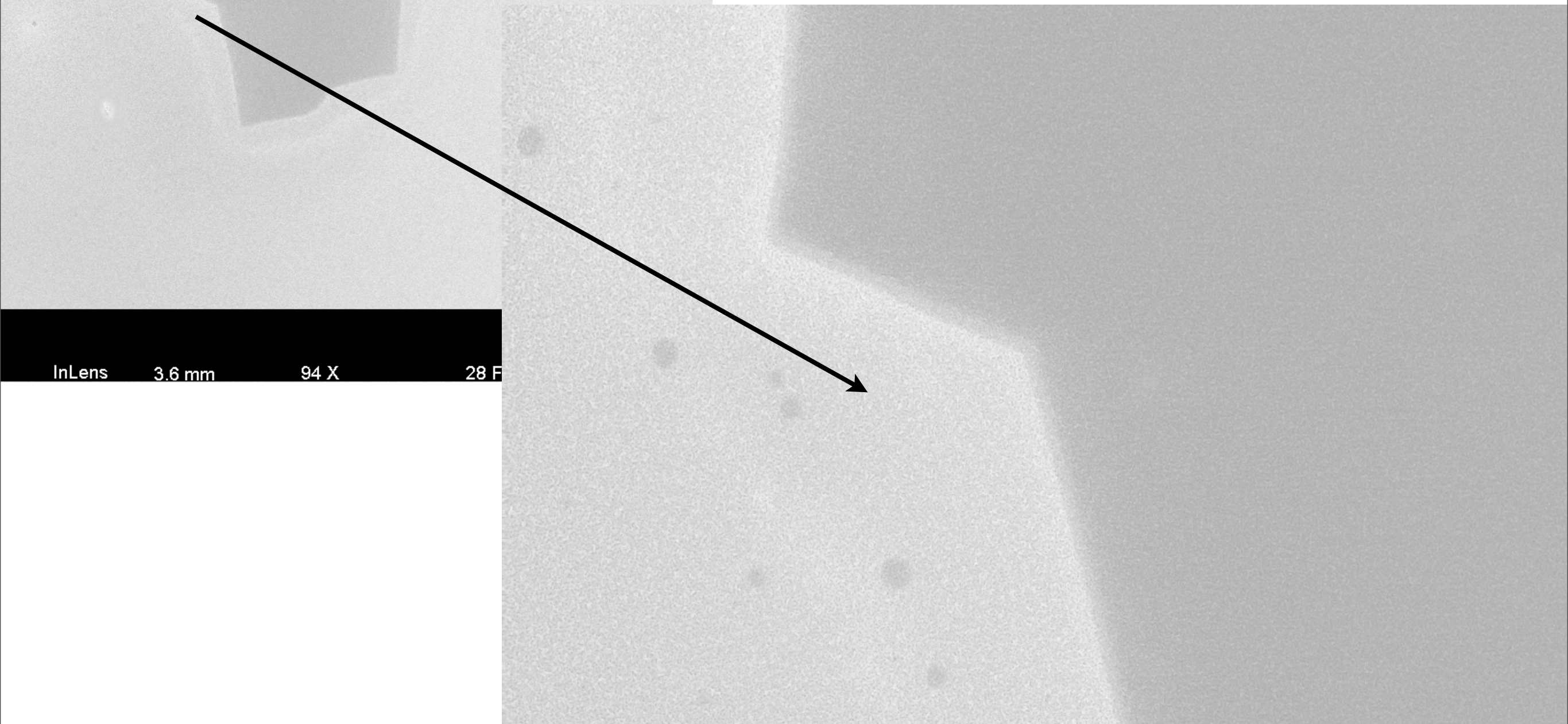
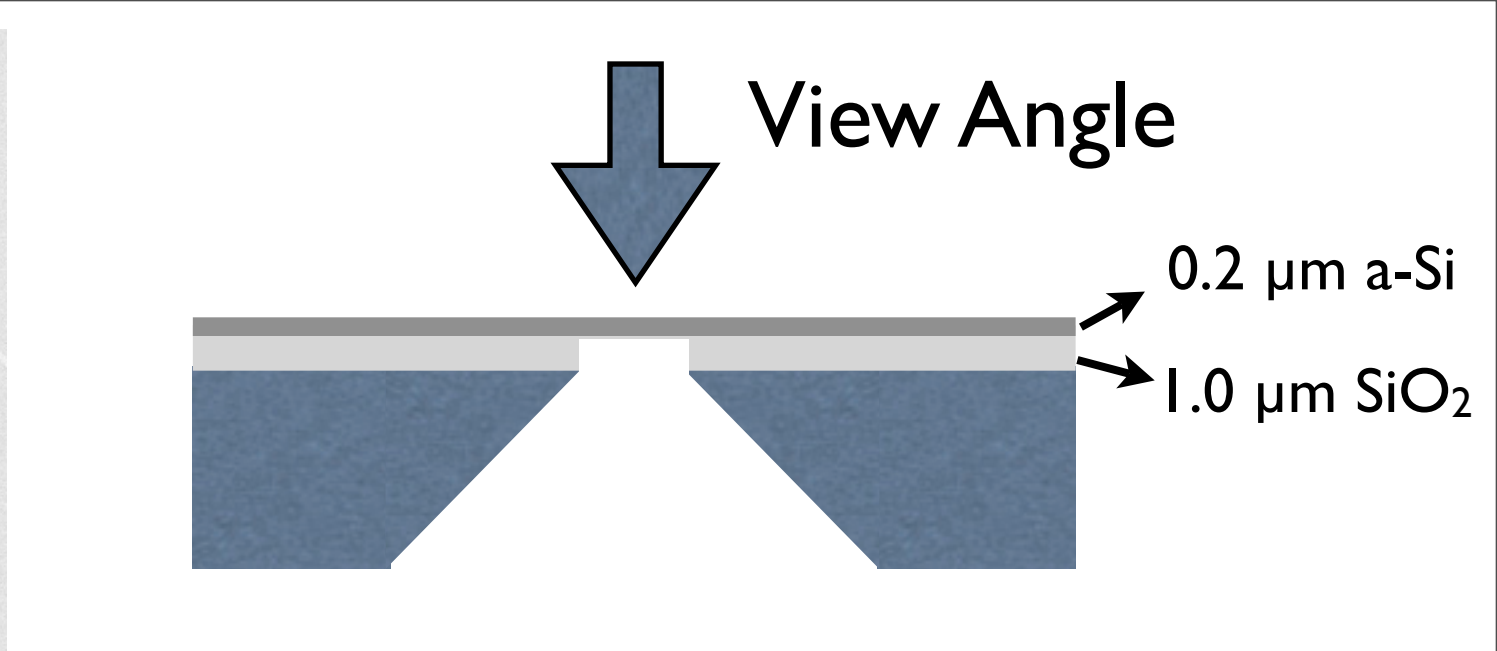


15s etch in 50:1 vol 50%HF:30%H₂O₂



15s etch in 50:1 vol 50%HF:30%H₂O₂





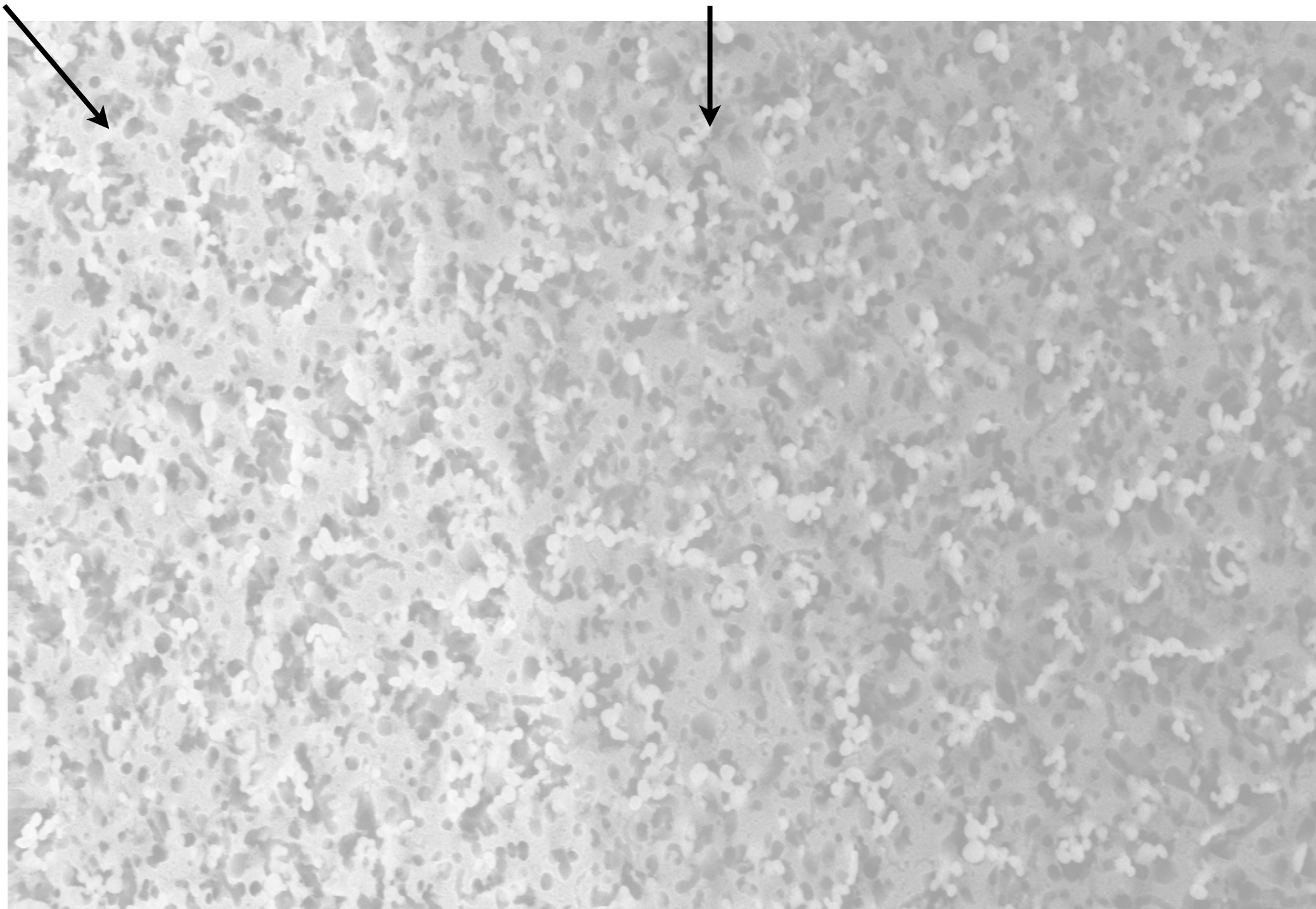
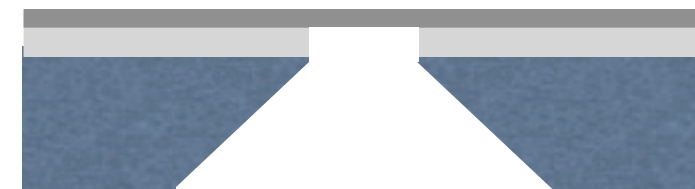
InLens 3.6 mm 94 X 28 F

20 μm 5.00 kV InLens 3.6 mm 666 X 28 Feb 2011 JWIN

Over substrate

Membrane

View Angle



1 μm

5.00 kV

InLens

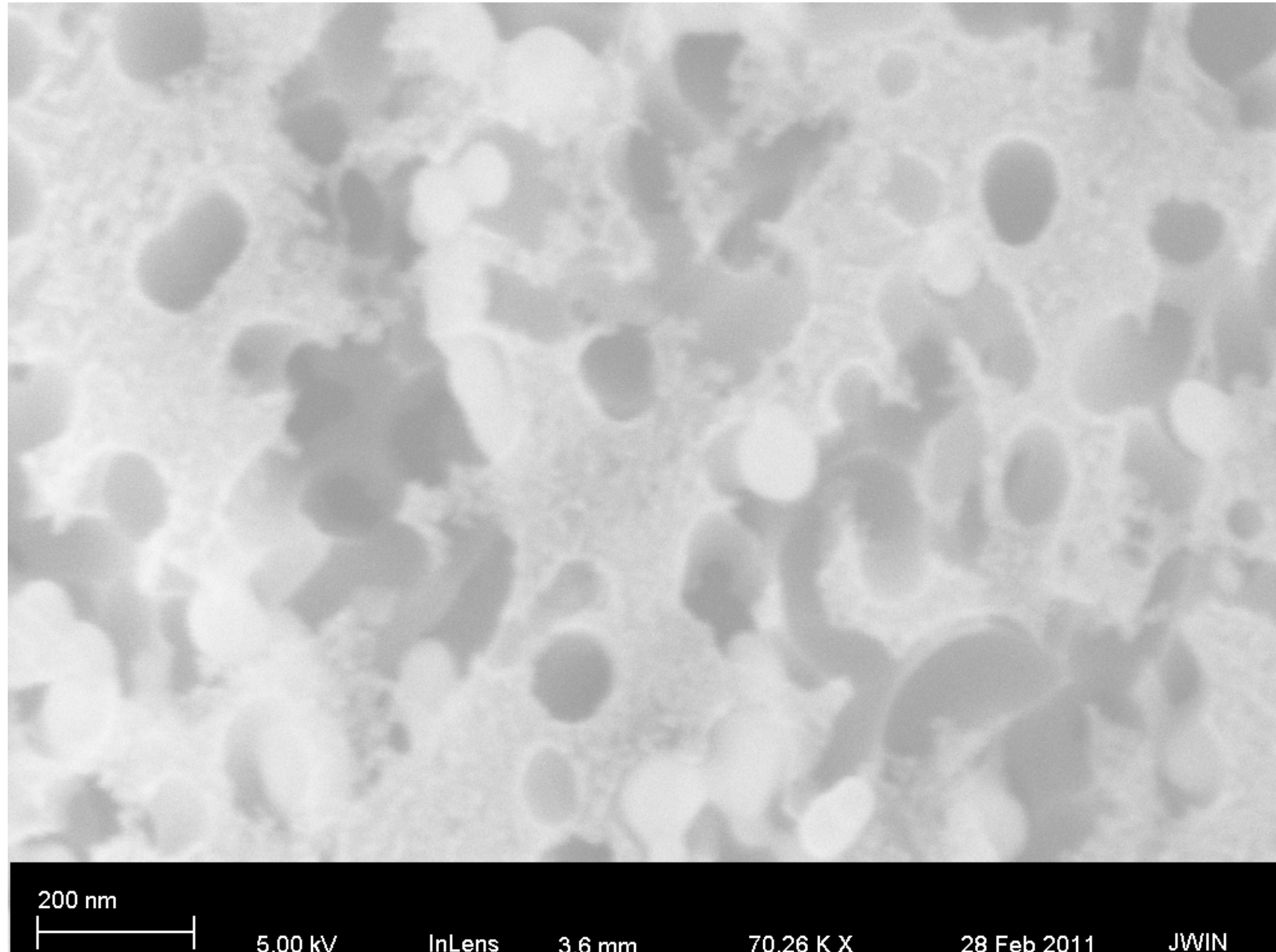
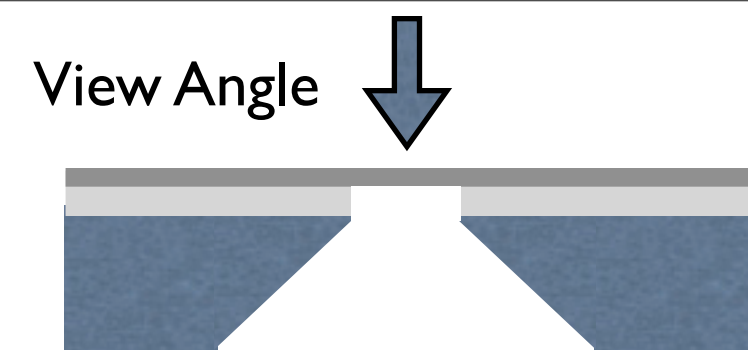
3.6 mm

9.95 K X

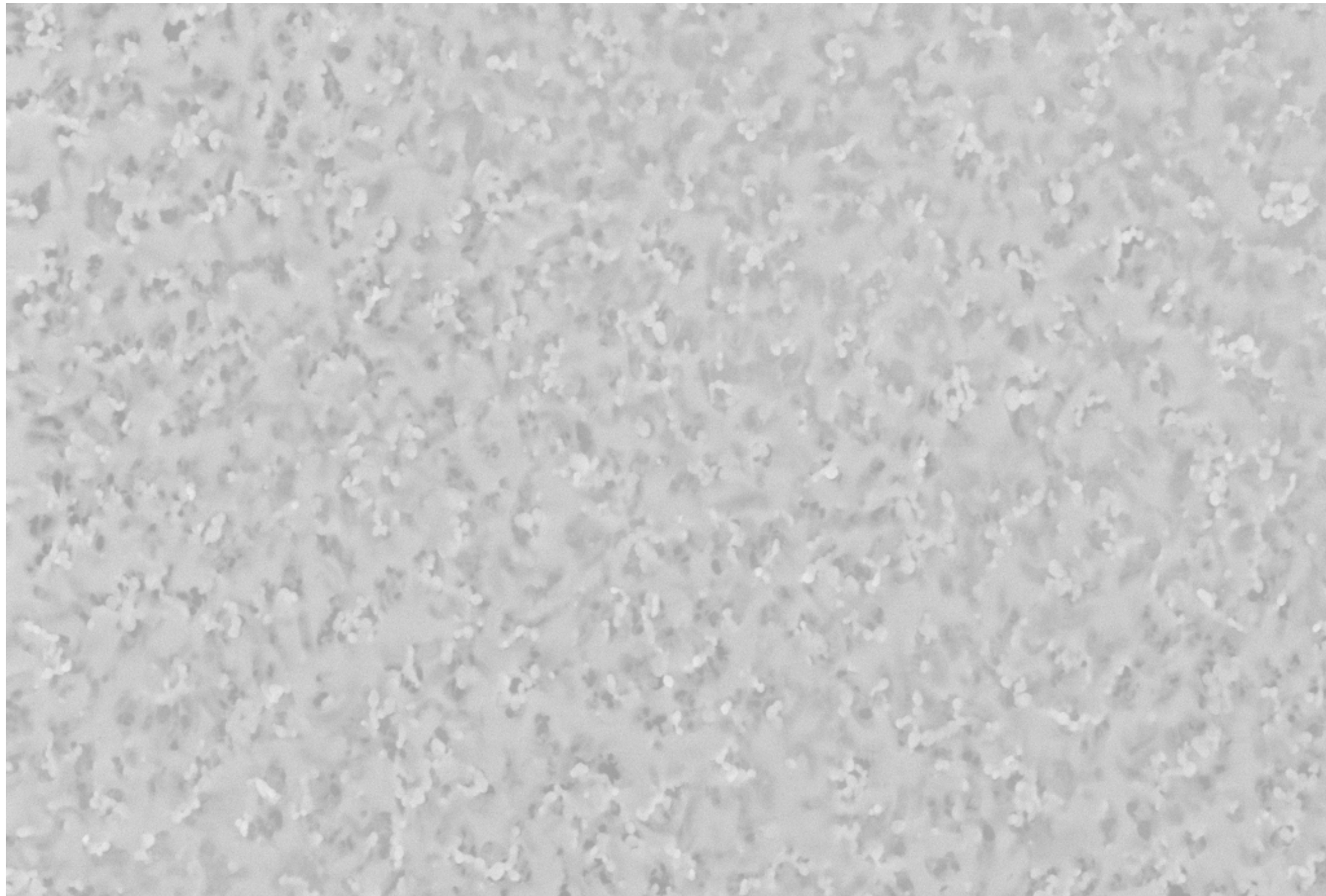
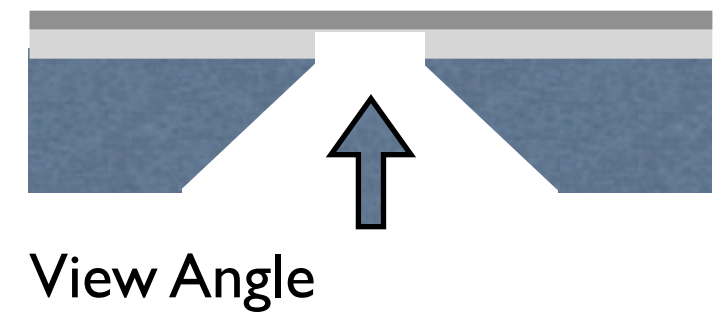
28 Feb 2011

JWIN

Membrane



Membrane



1 μm

5.00 kV

InLens

3.5 mm

8.42 K X

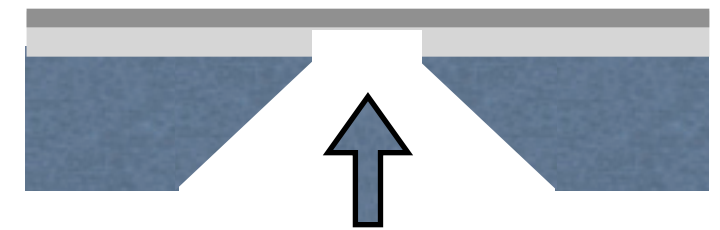
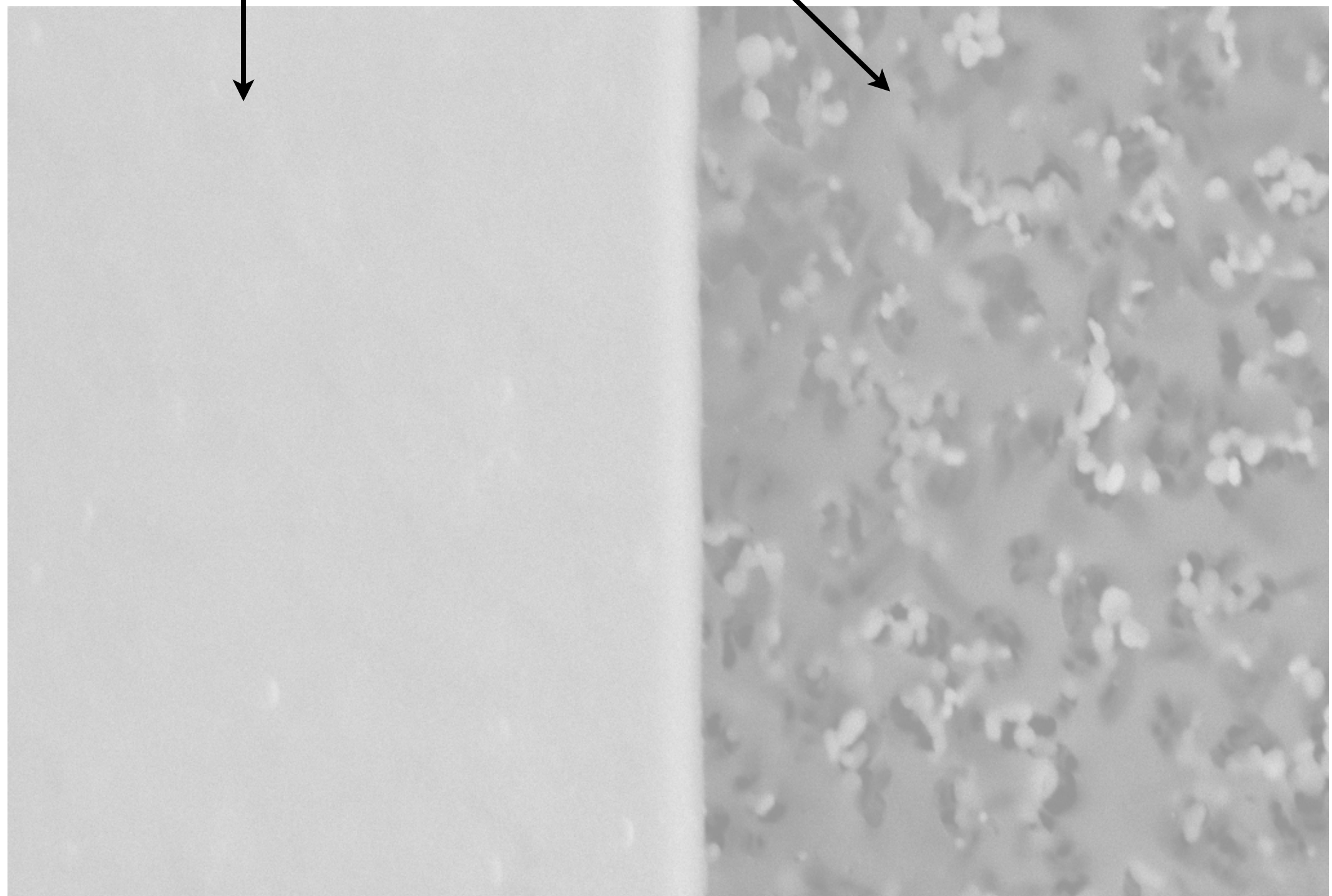
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Substrate

Membrane

View Angle



1 μm

5.00 kV

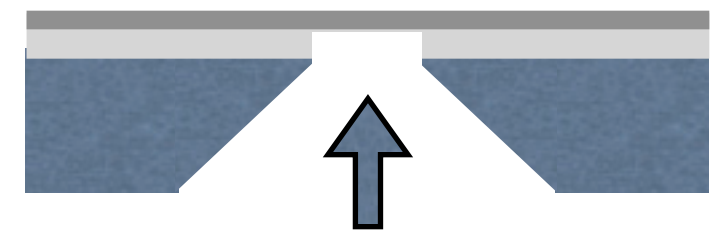
InLens

3.6 mm

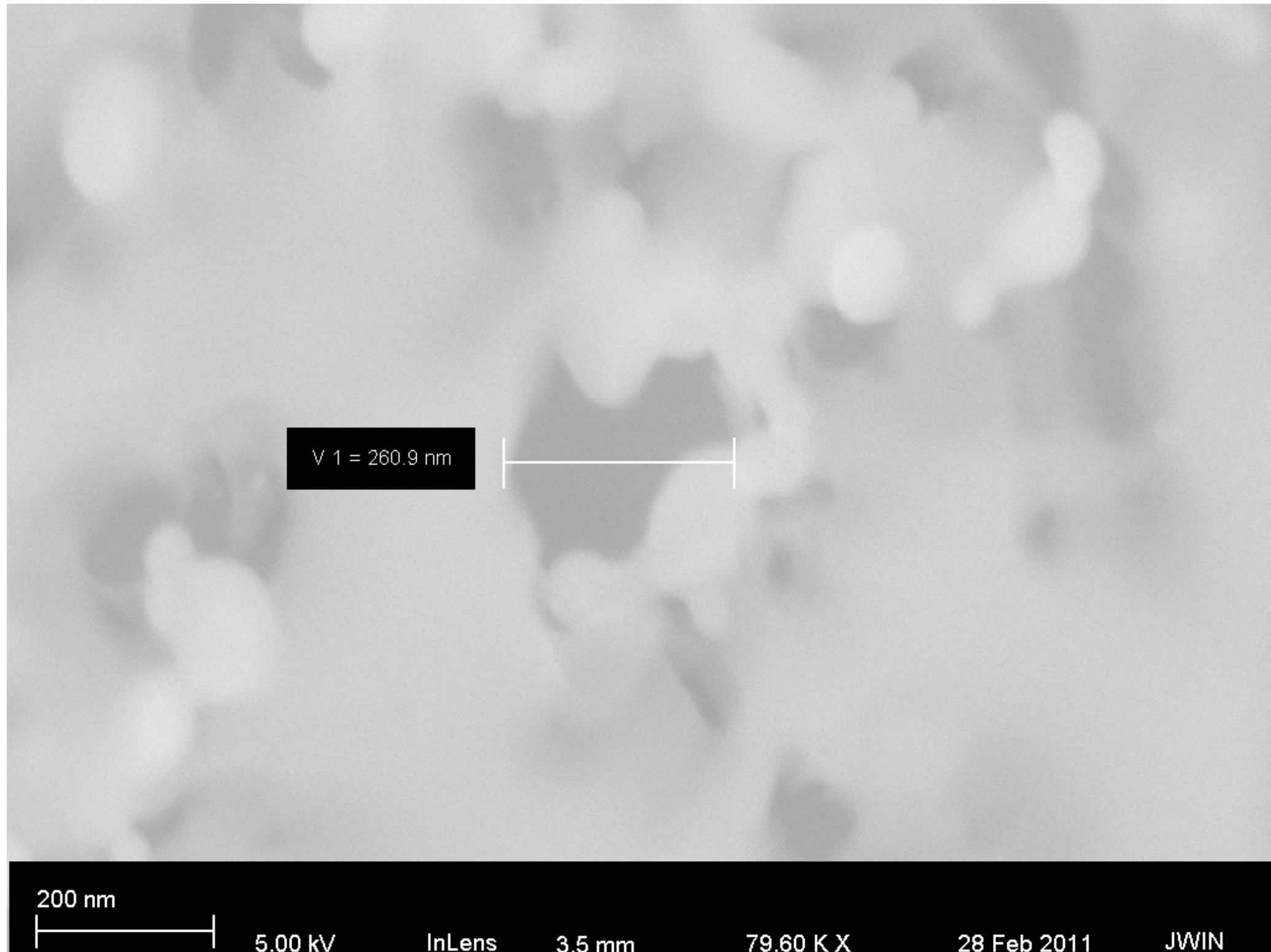
16.39 K X

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View Angle



V 1 = 260.9 nm

200 nm

5.00 kV

InLens

3.5 mm

79.60 K X

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What's Next?

- Answer question: “who cares?”
 - Possible answer
 - pore radius and surface density only limited by metal particle deposition technique
 - membrane thickness variable
- 200 μm DSP substrates with ??? mask
- Test mechanical properties